IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

OFFICIAL

Applicant(s):

Yoo, Woo Sik

CENTRAL FAX CENTER

Assignee:

WaferMasters, Inc.

JAN 2 2 2004

Title:

Gas-Assisted Rapid Thermal Processing

Serial No.:

10/005,827

Filing Date:

November 8, 2001

Examiner:

Trinh, M.

Group Art Unit:

2822

Docket No.:

M-11914 US

Irvine, California January 22, 2004

Mail Stop After Final Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

CERTIFICATION OF FACSIMILE TRANSMISSION

I hereby certify that the following Response to Office Action (4 pages), including Transmittal

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Office at facsimile telephone number (703) 872-9306 on the date shown below.

Dated: January 5, 2004

Theodore P. Lopezi Reg. No. 44,881

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Fax to USPTO

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S rial No. 10/005,827

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January 22, 2004

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Dear Sir:

Transmitted herewith are the following documents in the above-identified application:

- (1) Certification of Facsimile Transmission;
- (2) This Transmittal Letter (in duplicate); and
- (3) Response to Office Action (4 pages).

No additional fee is required.

The fee has been calculated as shown below:

CLAYMS AS AMENDED

	Claims Remaining After Amendment		Highest No. Previously Paid For		Present Extra		<u>Rate</u>		Additional Fee
Total Claims	8	Minus	20	=	0	x	\$18.00	\$	0.00
Independent Claims	2	Minus	4	=	0	x	\$84.00	\$	0.00
	Fee of for the first filing of one or more multiple dependent claims per application								
Fee for	Request for Extension	of Time						\$	0.00
	Total additional fee	for this A	mendment:					S	0.00
filing	Conditional Petition for Extension of Time: If an extension of time is required for timely filing of the enclosed document(s) after all papers filed with this transmittal have been considered, an extension of time is hereby requested.								
Please	Please charge our Deposit Account No. 50-2257 in the amount of								
	harge any additional fe at No. 50-2257	es required	and credit any o	vеграу	ment to o		2		•
					Λ.	/ T	otal:	\$	<u>\$0.00</u>

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Adriane Giberson

January 22, 2004

y submitted,

The Gore P: Lopez Attorney for Applicants Reg. No. 44,881

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Tota	l Claims	8	Minus	20	=	0	x	\$18.00	\$		0.00
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	Fee of for the first filing of one or more multiple dependent claims per application								\$		
	Fee for Request for Extension of Time								\$		0.00
	Total additional fee for this Amendment:								\$		0.00
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RESPONSE TO OFFICE ACTION

OFFICIAL

Dear Sir:

In response to the Office Action dated October 22, 2003, Applicants submit the following amendments and remarks.

IN THE CLAIMS

- 1. (Canceled)
- 2. (Currently Amended) A system for processing a semiconductor device, the system comprising:
 - a processing chamber; and
- a first plate positioned within said processing chamber and defining a first internal cavity configured to receive a first gas through a first passage into said first internal cavity at a first temperature and to emit said first gas from said first internal cavity at a second temperature through a second passage; and

a second plate disposed adjacent to said first plate, <u>said first plate and said</u>

<u>second plate defining a processing area therebetween</u>, wherein said second plate

<u>defines</u> <u>defining</u> a second internal cavity configured to receive a second gas through a

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Serial No. 10/005,827

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